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# High-density Nanoporous silicon decoupling capacitors

Murata Integrated Passive Solutions (MIS)

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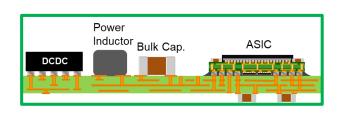


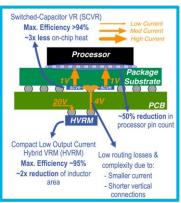


#### **Outline**



- Introduction / Thoughts sharing
- II. Silicon Capacitors: 5W (Where, Who, When, Why, What)
- III. 3D Nanoporous Silicon capacitors for Power applications (PDN, iVR)
- IV. Conclusion



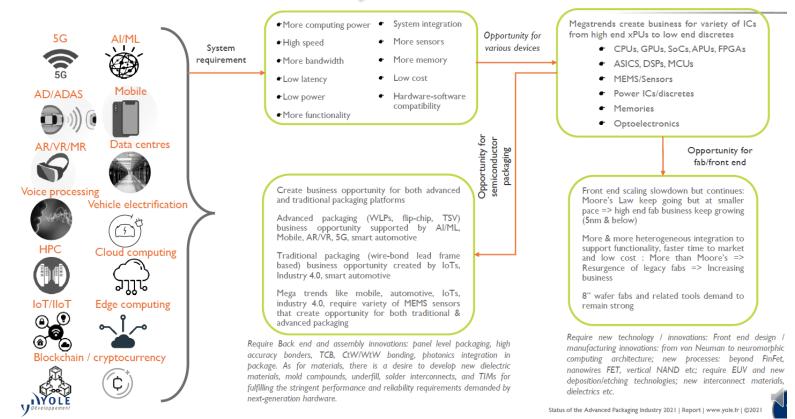




#### I. Introduction







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Source: Yole Développement

### II. Murata Integrated Passive Solutions\_ Where?







## II. Silicon Capacitors technology\_Who? When?



High Density



**High Capacitance GRM Series** (2.5V~100V, ~220uF)

**Polymer Electrolysis ECAS Series** 

(2.5V~25V, ~470uF)

**EDLC** DMF Series (~1000mF, 4,2V)

Low ESL **LLL/LLD Series** (~4.3uF, 9.2uF)

Consumer

Factory Automation, PLC,

Industry

LED lighting, TV, Air conditioner

Smartphone, Tablet, Wearable

(25V~1kV, ~100uF) **Embedded** GRU/LLU Series 🛰 **Implant Class D GCR/GCH Series** (ISO13485)

**High Reliability** 

**Ultra Small Size** GRM01/02 Series (008004, 01005)

Non Magnetic MA Series (MRI application )





Imaging Therapy, Hearing Aid, Clinic System Wind / PV Power

**Metal Terminal** 

KRM Series

(110um~, Cu VIA Connection)

Healthcare

PA High Q

(250V~500V. 1GHz~10GHz)

Optical Transceiver

**GMA/GMD Series** 

(Wire Bonding, Au Electrode)

**GQM Series** 

Generation, Oil/Gas System **Energy** 



**RDE Series** 



Ultra High Voltage **DHS/DHK Series** (DC10~50kV,AC10~25kV)

**High Voltage DHR Series** 



**Automotive Grade** GCM Series

(ISO9001, AEC-Q200, TS16949)

Safety Recognized **DE Series** 

(13 countries Safety Approved, X2/Y1/Y2)

SNUBBER (SHIZUKI)

MIC-UV Series

(~1.200V, ~1.600uF)

(~1.600V, ~4uF)

**High Power EVC Series** 

(~1,600V, ~4uF)

DC-LINK (SHIZUKI) MEC-DL/HV Series

**High Power Conversion** 

**Ultra High Voltage, Communication** 

Wrong choice of passives can impact and limit the final application



**Miniaturization** 

Low profile Low FSI

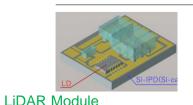


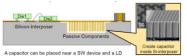
Low ESR High Reliability Mechanical strength

High Stability

### II. Silicon Capacitors technology\_ Where?











**Optical** transceivers











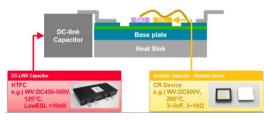
**UBB** 



**DC-DC** Converter 100MHz



High voltage DC-DC Converter SiC /GaN





Medical/Healthcare



**IOT & Communication** 

Neurostimulation module

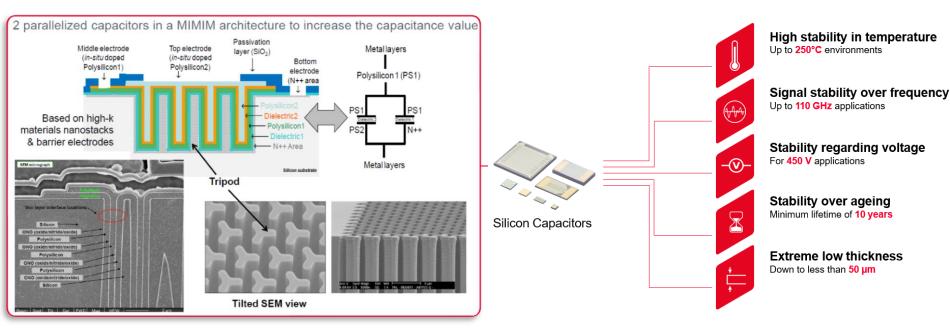






### II. What's Silicon Capacitors Technology?



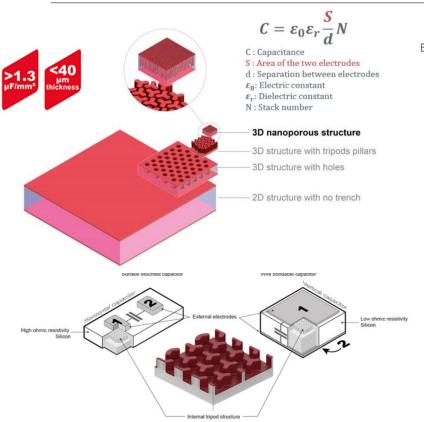


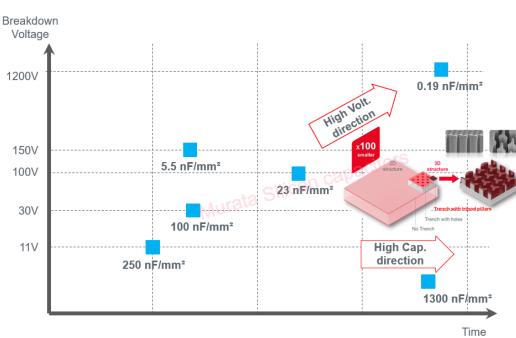
Murata is committed to a vision of developing innovative integrated Silicon capacitors to match the requirements and trends of SOC



### II. What's Silicon Capacitors Technology?







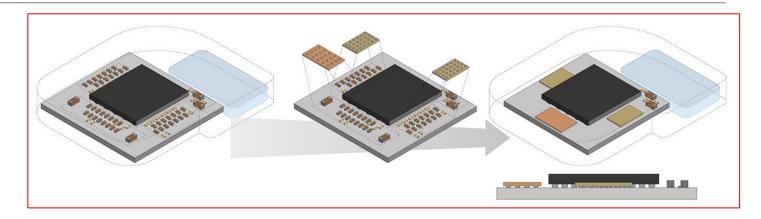
#### Silicon Capacitors extending MLCC portfolio



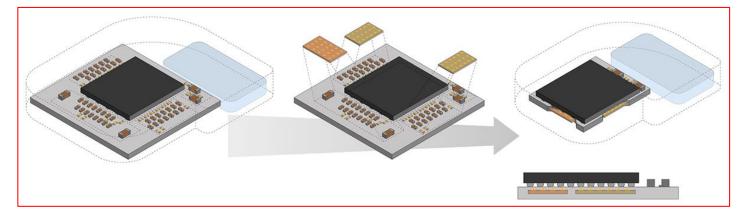
### II. What's Silicon Capacitors Technology?



Die Side



Land Side or Embedded

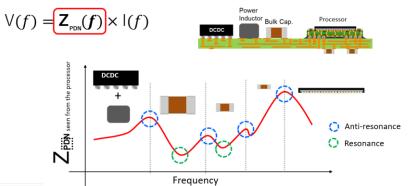




### III. PDN\_di/dt Mitigation



- Workloads exert excessive load transients and instability in the power supply network → variation in CPU activity may cause droop with steep slopes
- The di/dt events of CPUs induces voltage transients that need to be margined for, at the cost of power and performance
- Higher performance cores switch more current, inducing deeper droops. This impact is amplified at lower operating voltages as required by scaling trends
- → There is a need for an efficient PDN decoupling strategy



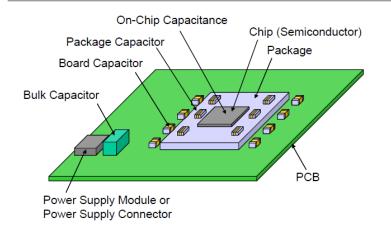


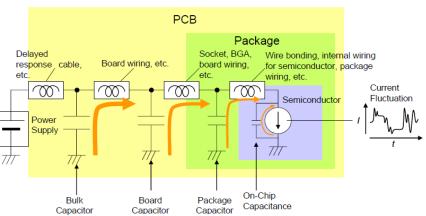
Need to take care of antiresonance and resonance to mitigate voltage noise



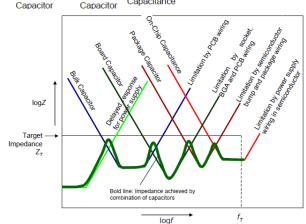
### III. PDN\_Application







- Power supply impedance must be made small over a wide frequency range
- One capacitor cannot achieve the necessary impedance, multiple capacitors are positioned hierarchically to achieve the target power supply impedance
- Due to space constraints, on-chip capacitance is not enough to reduce impedance at high frequencies.

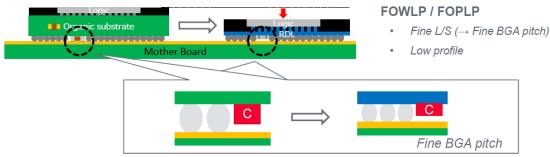




### III. PDN\_Trends and Requirements



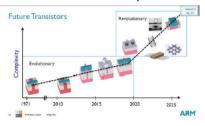
#### **Thickness**



#### Low profile capacitor is needed

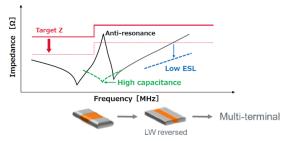
#### <u>ESL</u>

#### Microfabrication of process



 $10~nm \rightarrow 7~nm \rightarrow 5~nm...$ 

#### Lower target impedance



Low ESL capacitor is needed

#### **General Trends for Mobile & HPC**

- Higher functionality
- Scaling
- Increase in Power density

#### **General requirements for PDN**

- More stability & flat design
- Lower Z design at high frequency
- Lower Z design at anti-resonance



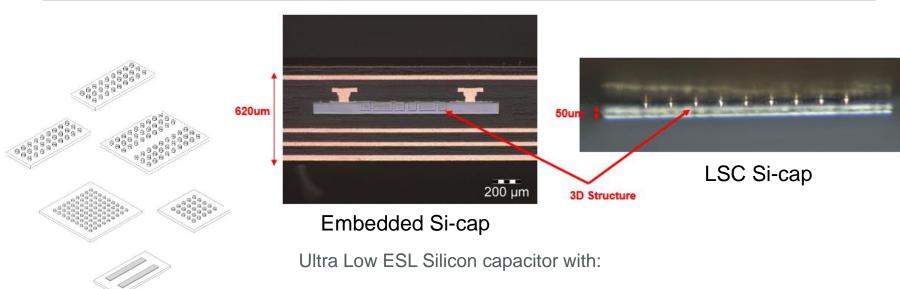
#### **Needs for Capacitors**

- Extreme Low ESL
- Extreme Low profile (Die, Terminal)
- High capacitance
- Adjustable ESR



### III. PDN\_Murata's UESL® family solutions





- State of the art density of >1300 nF/mm² in Silicon
- 1 μF in ultra compact 0404 form factor
- Ultra-low ESL (< 5 pH) and ESR (< 5 mΩ)</li>
- < 50 µm thickness
- Mechanical robustness



#### III. PDN\_Benefits



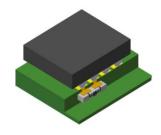
#### Si-Caps help reducing ESL

#### Landside packaging

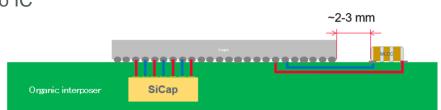
- Si-Caps intrinsic ESL is lower than MLCC
- Assembly ESL (parasitic) is reduced
  - Multi-terminals generate smaller current loop → lower ESL (shorter distance between pads)
  - Low-profile enables integration closer to IC

#### Embedded packaging

Ability to reduce substrate X/Y size



Source:https://www.murata.com/eneu/products/capacitor/siliconcapacitors/ov erview/medical



Decoupling cap	Parasitic from assembly	Cap intrinsic ESL	Conclusion
MLCC die-side	High ESL high distance - Underfill	High ESL	Standard
SiCap embedded	Low ESL close to IC	Low ESL Multi-terminals Adjacent opposite loops	Improvement

## III. PDN\_Multi-terminal and array structure



Multi-terminal is important to get low ESL.

Array structure offers high flexibility for PDN design

Surface

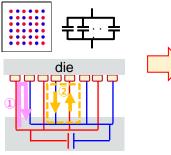
Current

1GHz

distribution @

Two-terminal Two-terminal die die pin Capacitor + current path current direction -29.6446 24.5935 22.0680 19.5424

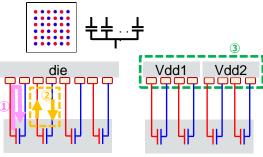
Multi-terminal



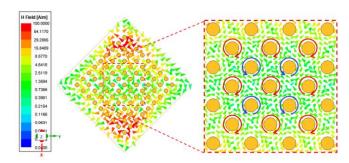
- Loop decrease(1)
- Counteract electromagnetic wave(2)
- →Low ESL in capacitor Low inductance of wire

Magnetic field distribution @ 1GHz

#### Array structure



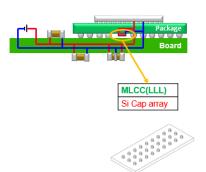
- Loop decrease(1)
- Counteract electromagnetic wave(2)
- →Low ESL in capacitor Low inductance in wire
- Capability to connect different power domains(3)
- →Flexibility of AP design

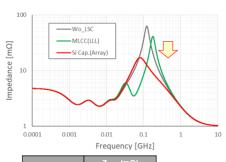




### III. PDN\_Si-caps improve system performance

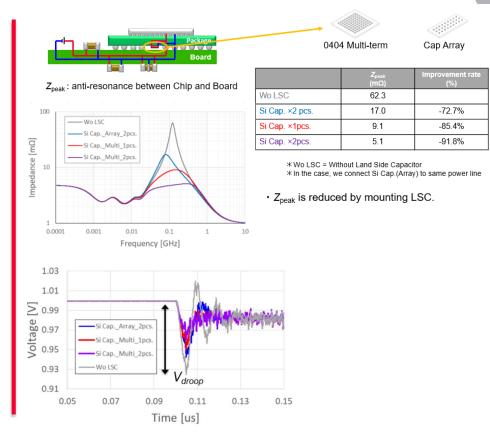






	$Z_{peak}$ (m $\Omega$ )	
Wo LSC	62.7	
MLCC(LLL)	41.2	-24.2 mΩ
Si Cap.(Array)	17.0	

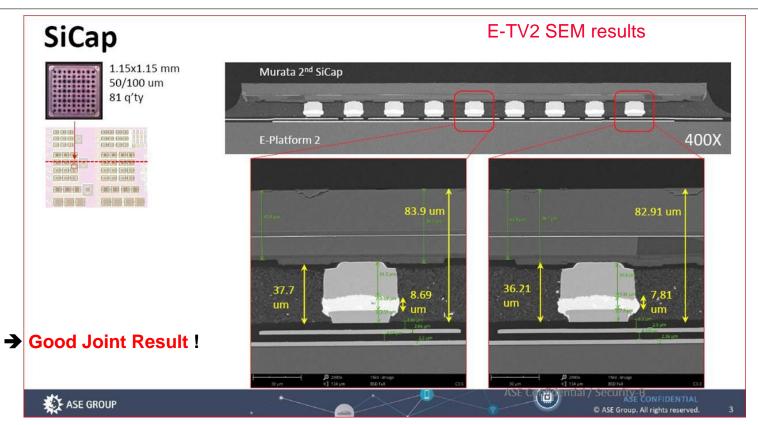
- Abrupt changes in processor activity induce large current transients in the power delivery network
- There is a need to reduce losses → provide better and more granular regulation to the processor cores





## III. PDN\_Assembly evaluation



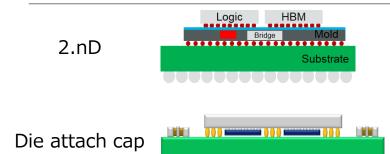






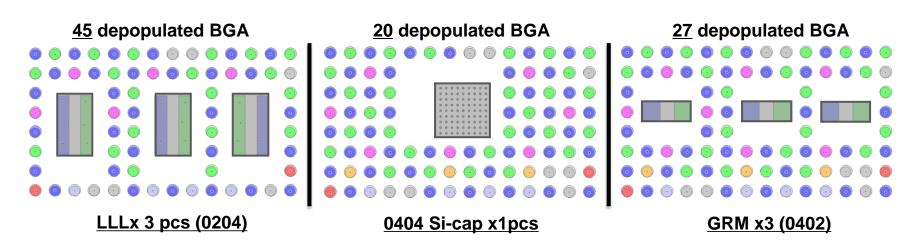
### III. PDN\_Advanced packaging





Power Integrity can be improved using specific cap:

- DC~1MHz Standard (High capacitance)
- 0.1 MHz Multi-terminal (Low inductance)
- 25 MHz Package Cap (Thin and Embedded cap)
- 100s MHz Si Multi-terminal 3D cap



### III. iVR\_Traditional Power Delivery



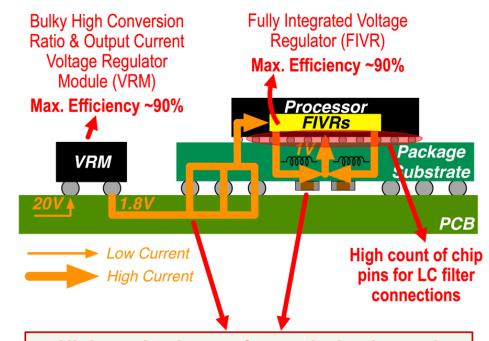


Prof. Hanh-Phuc Le and his team







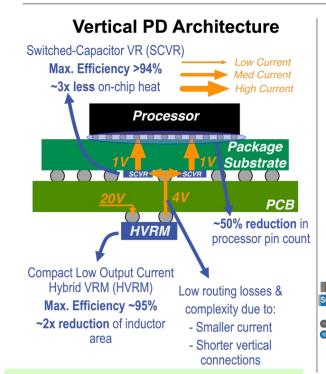


- High routing losses & complexity due to the lateral distribution of very high currents
- Overall System Efficiency ~80%



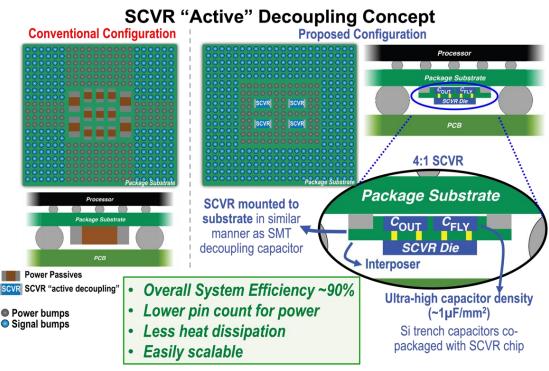
#### III. iVR\_ Approach based on Two-Stage Vertical PD and Management with Heterogeneous 3D Implementation





- ~2x reduction in package PDM pins
- 4x interconnect loss reduction:
- ~1.5x increase in available data IO pins.

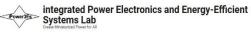




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Global Research Collaboration



### III. iVR\_ New Approach

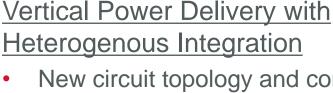


### UC San Diego

Prof. Hanh-Phuc Le and his team

**Unpublished Materials** Will be published at ISSCC Feb. 2023

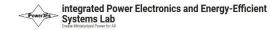
**Confidential – Unpublished materials!** 



- New circuit topology and control
- Switched capacitor for the last stage
- Integrated passive devices (IPDs)
- $>1 uF/mm^2$
- Silicon interposer for packaging
- Target: 2 A/mm<sup>2</sup>
- 87% total efficiency, with 94% for HVRM and ~93% for SCVR
- Accepted to ISSCC 2023







### VI. Conclusion\_On-package Si-cap for CPU

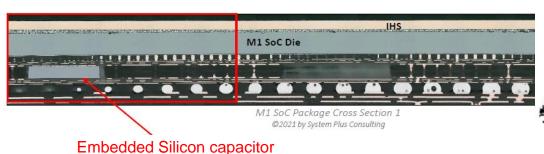






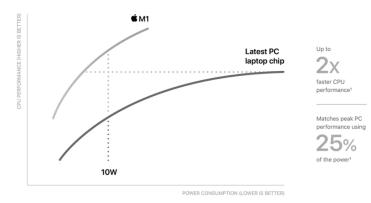
Source: https://www.apple.com/fr/newsroom/2020/11/apple-unleashes-m1/

#### 4 Land Side + 6 Embedded Silicon capacitors



Source: SystemPlus consulting

#### CPU performance vs. power



DRAM memory

M1 Processor Die

M2 Processor Die

SYSTEMPlus

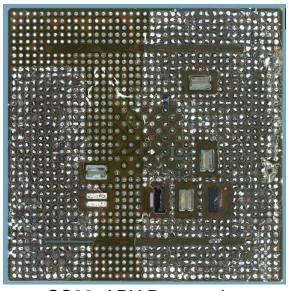
Bottom Package
Silicon Capacitor

Silicon Capacitor



### VI. Conclusion\_ On package Si-cap for APU





GS22\_APU Bottom view



Source: SYSTEMPlus

Silicon capacitors → enabling innovation and push the limits





#### Thanks a lot for your time and attention!

Contact: mohamed.jatlaoui@murata.com





